

ALD Al₂O₃ (TMA+H₂O-300C) + etch in BCl₃

Original (nm)	Thickness (nm)	Time (s)	Etch Depth (nm)	
53.1	42.3	12	10.8	Al ₂ O ₃ 250W
53.1	29.0	24	24.1	
53.1	17.7	36	35.3	
53.1	6.2	48	46.9	
53.5	34.5	30	19.0	Al ₂ O ₃ 50W
53.5	24.5	45	29.1	
53.5	14.3	60	39.3	
53.5	4.9	75	48.6	

Al₂O₃ Etch Rate in BCl₃ ICP2

